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## **INFORMATION DISCLOSURE STATEMENT BY APPLICANT**

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Sheet 1 of 3

Complete if Known	
Application Number	09/922,426
Filing Date	August 3, 2001
First Named Inventor	Trulson et al.
Art Unit	1639
Examiner Name	Maurio Garcia Baker Celsa
Attorney Docket Number	3305.1

## **U.S. PATENT DOCUMENTS**

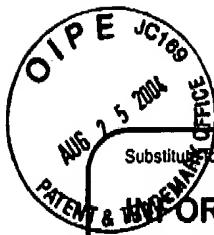
## **FOREIGN PATENT DOCUMENTS**

Examiner Signature		Date Considered	11/3/04
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## INFORMATION DISCLOSURE STATEMENT BY APPLICANT

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Sheet

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NON PATENT LITERATURE DOCUMENTS			
Examiner Initials *	Cite No. <sup>1</sup>	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T <sup>2</sup>
<i>MR</i>	8	Grifling and West IEEE Electron Device Letters EDL-4(1): 14(1983).	
<i>MR</i>	9	GHANDI, VLSI Fabrication Principles, 1983, Chapter 10.	
<i>MR</i>	10	HOFER et al., Contrast enhanced uv lithography with polysilanes, Advances in Resist Technology, 1984, 108-16, SPIE Vol. 469.	
<i>MR</i>	11	HALLE, L., et al., J. Vac. Sci. Technol. B., 1985, 323-326, Vol. 3(1).	
<i>MR</i>	12	SHEATS, et al., SPIE Proc. 1986, 631, 171	
<i>MR</i>	13	UCHINE, et al., Proc. Poly. Mat. Sci. And Eng., 1986, 55, 604-607.	
<i>MR</i>	14	PAUL R. WEST, et al., Contrast Enhanced Photolithography: Application of Photobleaching Processes in Microlithography, J. Imaging Science, March/April 1986, 65-68, Vol. 30, No. 2.	
<i>MR</i>	15	DON R. STROM, Optical Lithography and Contrast Enhancement, Semiconductor International, May 1986, 162-87.	
<i>MR</i>	16	ENDO, et al., High aspect-ratio resist pattern fabrication by alkaline surface treatment, J. Vac. Sci. Technol. B., 1989, 1076-79, Vol. 7(5).	
<i>MR</i>	17	UCHINO, SHOU-ICHI et al., Synthesis of new metal-free diazonium salts and their applications to microlithography, Journal of Photopolymer Science and Technology (1989); 2 (1): 255-299.	
<i>MR</i>	18	REISER, et al., Photoreactive Polymers: the Science and technology of Resists, 1989, 226-29.	

Examiner Signature	<i>Brent C.M.</i>	Date Considered	11/13/04
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Attorney Docket Number

3305.1

**NON PATENT LITERATURE DOCUMENTS**

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MC	19	SALAMY, et al., Proc. Electrochem. Soc., 1989, 90:36.	
MC	20	DURAND, et al., Nucleic Acids Res., 1990, 6353-59, Vol 18., No. 21.	
MC	21	TOSHIHIKO TANAKA, et al., Sub-Halfmicron Lithography Using a High-Contrast i-Line CEL, Japanese J. Applied Physics, Sept. 1990, 1860-61, Vol. 29, No. 1.	
MC	22	R. PFORR, et al., Contrast enhancement of the resist latent image using exposure induced absorption amplification – fundamental, modeling, and applicability, Microelectronic Engineering, 1992, 321-328, Vol. 17.	
MC	23	DAVID M. TEEGARDEN, et al., Contrast Enhancement Lithography System Based on Pyridinium Dye Bleach Chemistry, J. Imaging Science and Technology, 1993, 149-155, Vol. 37, No. 2.	
MC	24	THOMPSON, L.F., et al., Introduction to Microlithography, America Chemical Society, 1994 212-232.	
MC	25	HUANG, Proc. SPIE – Int. Soc. Opt. Eng., 1999, 3678, (Pt. 2) 340-51.	

Examiner Signature

Date Considered

8/3/04

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